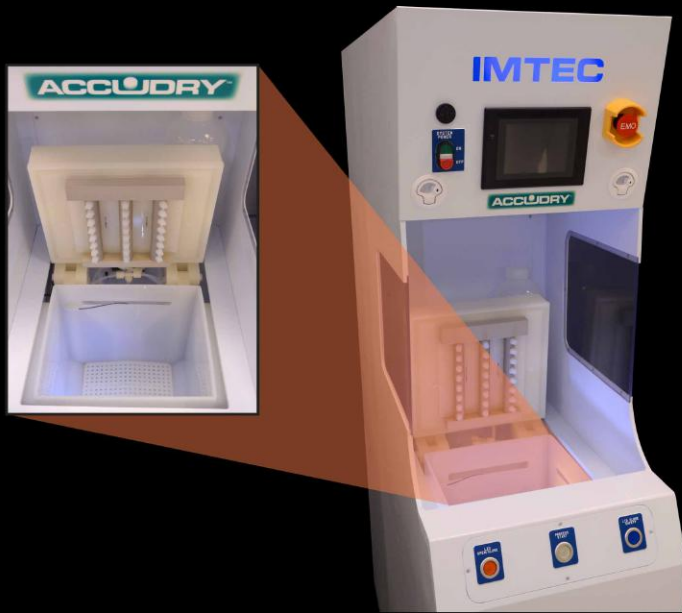


# ACCUDRY™

## IPA Vapor Dryers

*Damage and watermark free substrate drying*



### Wafer Drying, Engineered Right

As any process engineer can tell you, wafers are only as clean as their last process. That's why the Accudry utilizes the latest in alcohol vapor drying technology to ensure that the last step of your critical process results in clean, damage-free substrates. Using the Accudry after any wet process can improve the performance of ICs, solar cells, fuel cells, MEMS, disk drives, and many more.

### How Does the Accudry Work?

The Accudry uses room-temperature IPA vapor to rapidly displace water from the wafer surface until it is completely dry. This technique yields substrates that are watermark-free with extremely low particle counts and zero feature damage.

### No Spinning, No Moving Parts

Alcohol vapor drying is ideal for today's thinner substrates. No moving parts or mechanical stress on the wafers means no costly breakage or damage.

### Ease of Use

The Accudry has been designed for ease of use and real world functionality. With programmable recipes and semi automation, operators require minimal training. Operating the Accudry is as simple as load, set, run.

### Highly Configurable

The Accudry can process a batch of 25 or 50 wafers depending on configuration. The dryers are configurable to accept one or two cassettes from 150mm to 300mm and can be produced as stand-alone units or integrated into wet processing stations for OEMs.

*All Accudry units are backed by Imtec's 40 Years of process module expertise and ISO 9001 quality certification.*



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# IMTEC®

## Engineered for Spotless Substrate Rinsing & Drying

### The Advantage

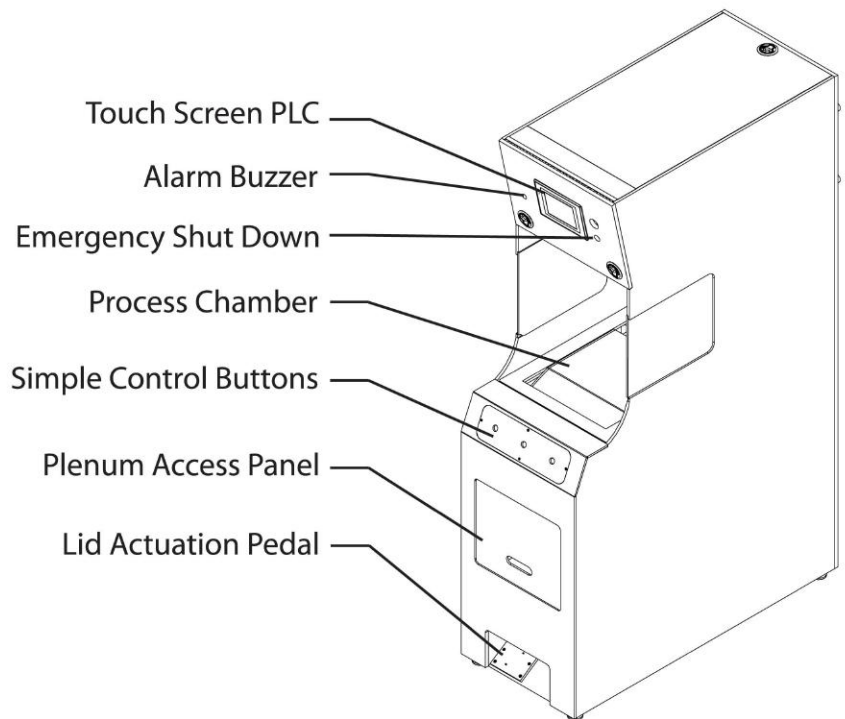
- No watermarks
- Molecular level drying
- No substrate breakage/feature damage
- Effectively dries high aspect ratio structures
- IPA is safely maintained at room temperature
- Extremely low chemical consumption
- Fits in the same footprint as a spin rinser dryer
- Capital cost savings:
  - Shorter process times
  - Reduced maintenance
  - Extremely price competitive

### Features

- Automatic, high volume, single or dual cassette configurations
- Adaptable to virtually any substrate material and/or shape
- Available as a stand alone unit or integrated into a wet station
- Programmable recipes including precise control of vapors and gasses
- User-friendly software with touch screen interface

### Options

- Quartz in-line water heater
- Integrated megasonic clean unit
- Fire suppression system
- Resistivity probe
- Connection for external IPA bulk fill module
- Custom options available upon request



### Available Sizes

Single / Dual 150mm Cassette  
Single / Dual 200mm Cassette  
Single / Dual 300mm Cassette  
Custom Sizes Upon Request

